
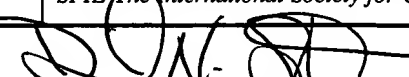
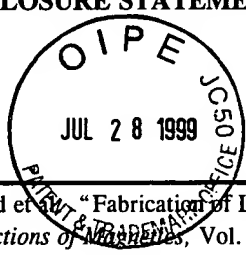
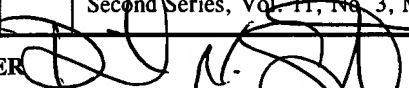


FORM PTO - 1449 INFORMATION DISCLOSURE STATEMENT				ATTORNEY DOCKET NO.: MIT-106 APPLICANT: Michael Mermelstein SERIAL NO.: 09/2746,601 FILING DATE: March 23, 1991 GRANTING OFFICE CENTER 2800 Assigned 3-23-99 2873					
				RECEIVED JUL 30 1999					
U.S. PATENT DOCUMENTS									
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE		
DNS	A1	Re. 35,930	10/20/98	Brueck et al.	430	311	04/22/96		
DNS	A2	5,771,098	06/23/98	Ghosh et al.	356	363	09/27/96		
DNS	A3	5,759,744	06/02/98	Brueck et al.	430	312	03/16/95		
DNS	A4	5,705,321	01/06/98	Brueck et al.	430	316	06/06/95		
DNS	A5	5,415,835	05/16/95	Brueck et al.	430	396	09/16/92		
DNS	A6	5,384,573	01/24/95	Turpin	342	179	03/17/93		
FOREIGN PATENT DOCUMENTS									
EXAM. INIT.		DOCUMENT NUMBER	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG Y/N
DNS	B1	WO 97/48021	12/18/97	PCT	603F	7/20	06/10/97	N	Yes
DNS	B2	GB 2142427A	1/16/85	UK	601B	11/30	5/21/84	N	Yes
OTHER ART, JOURNAL ARTICLES, ETC.									
EXAM. INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)								
DNS	C1	Anderson, et al. "Holographic lithography with thick photoresist," <i>Appl. Phys. Lett.</i> , Vol. 43, No. 9, November 1, 1983, pp. 874-876.							
DNS	C2	Brueck, S. "Imaging interferometric lithography," <i>Microlithography World</i> , Winter 1998, pp. 2-7.							
DNS	C3	Brueck, et al. "Interferometric lithography - from periodic arrays to arbitrary patterns," <i>Microelectronic Engineering</i> , 41/42 (1998), pp. 145-148.							
DNS	C4	Chen et al. "Interferometric lithography of sub-micrometer sparse hole arrays for field-emission display applications," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 14, No. 5, Sept/Oct 1996, pp. 3338-3349.							
DNS	C5	Chen et al. "Process development for 180-nm structures using interferometric lithography and I-line photoresist," <i>SPIE - The International Society for Optical Engineering</i> , Vol. 3048, March 10-11, 1997, pp. 309-318.							
EXAMINER 				DATE CONSIDERED 6/19/00					

FORM PTO - 1449		ATTORNEY DOCKET NO.: MIT-106
INFORMATION DISCLOSURE STATEMENT		APPLICANT: Michael Mermelstein
		SERIAL NO.: 09/2746,601
		FILING DATE: March 23, 1991 GROUP: ²⁸⁷³ Not Yet Assigned 3-23-99
DNS	C6	Farhoud et al. "Fabrication of Large Area Nanostructured Magnets by Interferometric Lithography," <i>IEEE Transactions on Magnetics</i> , Vol. 34., No. 4, Pt. 1, July 1998, pp. 1087-1089.
DNS	C7	Ferrera et al. "Analysis of distortion in interferometric lithography," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 14, No. 6, Nov/Dec 1996, pp. 4009-4013.
DNS	C8	Naqvi et al. "Diffractive techniques for lithographic process monitoring and control," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 12, No. 6, Nov/Dec 1994, pp. 3600-3607.
DNS	C9	Savas et al. "Large-area achromatic interferometric lithography for 100 nm period gratings and grids," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 14, No. 6, Nov/Dec 1996, pp. 4167-4170.
DNS	C10	Savas et al. "Achromatic interferometric lithography for 100-nm-period gratings and grids," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 13, No. 6, Nov/Dec 1995, pp. 2732-2735.
DNS	C11	Schattenburg et al. "Fabrication of high energy x-ray transmission gratings for AXAF," <i>SPIE-The International Society for Optical Engineering</i> , Vol 2280, pp. 181-190.
DNS	C12	Schattenburg et al. "Optically matched trilevel resist process for nanostructure fabrication," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 13, No. 6, Nov/Dec 1995, pp. 3007-3011.
DNS	C13	Spallas et al. "Field emitter array mask patterning using laser interference lithography," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 13, No. 6, Sept/Oct 1995, pp. 1973-1978.
DNS	C14	Zaidi et al. "Interferometric lithography exposure tool for 180-nm structures," <i>SPIE-The International Society for Optical Engineering</i> , Vol. 3048, March 10-11, 1997, pp. 248-254.
DNS	C15	Zaidi et al. "Multiple-exposure interferometric lithography," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 11, No. 3, May/Jun 1993, pp. 658-666.
EXAMINER 		DATE CONSIDERED 6/19/00

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